

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	42828	silicon adj (oxide dioxide) near5 (wafer substrate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/12/09 13:23
L8	4756	1 same implant\$5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/12/09 13:29
L9	1337	8 same (anneal\$3 heat\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/12/09 13:30
L10	204	9 same (remov\$3 near5 (oxide dioxide))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/12/09 13:30
L11	1	10 same (scrib\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/12/09 13:31